What Is Claimed Is:

1.   A method of fabricating a mask, comprising:

providing material and device data;

defining a first manufacturing model according to the

5   material and the device data;

performing a first process run of a first mask as defined

by the first manufacturing model;

collecting a first process data during the first process

run;

10   determining a backward modification data according to the

material, the device["device" lacks antecedent

basis], and the first process data;

modifying the first manufacturing model according to the

backward modification data to obtain a second

15   manufacturing model; and

performing a second process run of a second mask as defined

by the second manufacturing model.

2.   The method of claim 1, wherein the backward modification data determining step further comprises performing statistical process control analysis.

3.   The method of claim 1, wherein the material data comprises photoresist type, characteristics, production date, post coating decay, or batch relation data.

4.   The method of claim 1, wherein the device data comprises device type, mask layer, mask grade, option correction type, pattern loading or device loading data.

5.   The method of claim 1, wherein the first production data ["first production data" lacks antecedent basis] comprises exposure tool, etching chamber, etching time, tooling bias, batch relation, or inspection result data.

6.   The method of claim 1, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes a writing process for masks.

7.   The method of claim 1, wherein the manufacturing model

defining step further comprises defining a manufacturing model

that describes a baking process for masks.

8.   The method of claim 1, wherein the manufacturing model

5   defining step further comprises defining a manufacturing model

that describes a developing process for masks.

9.   The method of claim 1, wherein the manufacturing model

defining step further comprises defining a manufacturing model

that describes an etching process for masks.

10   10.   The method of claim 1, further comprising:

acquiring an inspection result of a preceding process run,

wherein the inspection result is an after-strip

inspection result;

determining a forward modification data according to the

15   first production data ["first process data"?] and the

inspection result;

determining a re-etch manufacturing model according to the

forward modification data; and

performing a re-etch process run of the first mask as

defined by the re-etch manufacturing model.

11. A method for controlling mask fabrication using

statistical process control analysis, comprising:

5   defining a manufacturing model;

performing a process run of a mask as defined by the

manufacturing model;

performing a fault detection analysis to reduce a bias in

the manufacturing model;

10   generating a fine-tuning signal in response to a result of

the fault detection analysis; and

adjusting the process run operation according to the

fine-tuning signal.

12. The method of claim 11, wherein the manufacturing

15 model defining step further comprises defining a manufacturing

model that describes a writing process for masks.

13. The method of claim 11, wherein the manufacturing

model defining step further comprises defining a manufacturing

model that describes a baking process for masks.

14. The method of claim 11, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes a developing process for masks.

15. The method of claim 11, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes an etching process for masks.

16. The method of claim 11, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes an stripping process for masks.

17. A mask fabrication system, comprising:

a processing tool for processing a mask;

a metrology tool, interfaced with the processing tool, for inspecting the mask and obtaining an inspection result;

a controller, coupled with the processing and metrology tools, for generating a manufacturing model of the processing tool and calibrating the manufacturing model according to a device data, a material data, and the inspection result of the mask.

18.	The system of claim 17, wherein the controller further performs statistical process control analysis.

19.	The system of claim 17, wherein the material data comprises photoresist type, characteristics, production date, post coating decay, or batch relation data.

20.	The system of claim 17, wherein the device data comprises device type, mask layer, mask grade, option correction type, pattern loading or device loading data.

21.	The system of claim 17, wherein the controller further defines a manufacturing model that describes a writing process for masks.

22.	The system of claim 17, wherein the controller further defines a manufacturing model that describes a baking process for masks.

23.	The system of claim 17, wherein the controller further defines a manufacturing model that describes a developing process for masks

24. The system of claim 17, wherein the controller further defines a manufacturing model that describes an etching process for masks.

25. The system of claim 17, wherein the controller further

5   performs steps of:

acquiring an inspection result of a preceding process run, wherein the inspection result is an after-strip inspection result;

determining a forward modification data according to the

10   first production data["first production data" lacks antecedent basis] and the inspection result;

determining a re-etch manufacturing model according to the forward modification data; and

performing a re-etch process run of the first mask as

15   defined by the re-etch manufacturing model.

26. A mask fabrication system, comprising:

a processing tool;

a monitor for monitoring an operating condition of the processing tool;

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a controller for determining an operating standard of the

processing tool and comparing it with the operating

condition thereof, and adjusting the processing tool

accordingly.

5   27.   The system of claim 26, wherein the processing tool

is a writer, baker, developer, etcher, or photoresist stripper.

28.   A computer readable storage medium for storing a

computer program providing a method for controlling mask

fabrication using statistical process control analysis, the

10   method comprising:

receiving a material, device and first process data of a

mask;

defining a first manufacturing model according to the

material and the device data;

15   determining a backward modification data according to the

material, the device, and the first process data; and

modifying the first manufacturing model according to the

backward modification data to obtain a second

manufacturing model; and

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issuing a process command, which directs a tool to process

a second mask according to the second manufacturing

model.

29. The storage medium of Claim 28, wherein the

manufacturing model defining step further comprises defining a

manufacturing model that describes a writing process for masks.

30. The storage medium of Claim 28, wherein the

manufacturing model defining step further comprises defining a

manufacturing model that describes a baking process for masks.

31. The storage medium of Claim 28, wherein the

manufacturing model defining step further comprises defining a

manufacturing model that describes a developing process for

masks.

32. The storage medium of Claim 28, wherein the

manufacturing model defining step further comprises defining a

manufacturing model that describes an etching process for masks.

33. The storage medium of Claim 28, wherein the method

further comprises:

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receiving an inspection result of a preceding process run,

wherein the inspection result is an after-strip

inspection result;

determining a forward modification data according to the

5   first production data and the inspection result;

determining a re-etch manufacturing model according to the

forward modification data; and

issuing a re-etch command, which directs a tool to re-etch

the first mask according to the re-etch manufacturing

10   model.

34. A computer readable storage medium for storing a
computer program providing a method for controlling mask
fabrication using statistical process control analysis, the
method comprising:

15   receiving a manufacturing model;

performing a fault detection analysis to reduce a bias in

the manufacturing model;

generating a fine-tuning signal in response to a result of

the fault detection analysis; and

adjusting the process run operation according to the fine-tuning signal.

35. The storage medium of Claim 34, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes a writing process for masks.

36. The storage medium of Claim 34, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes a baking process for masks.

37. The storage medium of Claim 34, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes a developing process for masks.

38. The storage medium of Claim 34, wherein the manufacturing model defining step further comprises defining a manufacturing model that describes an etching process for masks.